

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 08-047526

(43)Date of publication of application : 20.02.1996

(51)Int.Cl.

A61L 17/00

A61B 17/08

A61F 2/00

(21)Application number : 07-128397

(71)Applicant : GUNZE LTD

(22)Date of filing : 26.05.1995

(72)Inventor : OI SHIGEO  
OSHIMA HIROSHI  
HASHIMOTO SATOSHI

(30)Priority

Priority number : 06156353 Priority date : 03.06.1994 Priority country : JP

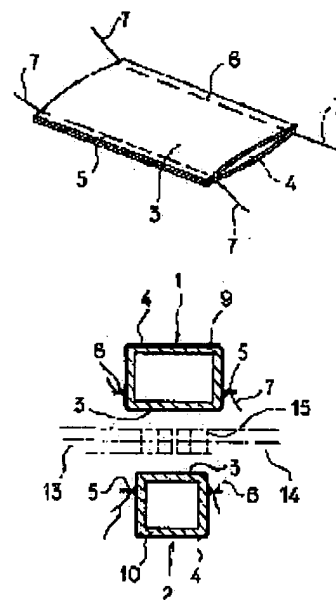
## (54) SUTURE PROSTHETIC MATERIAL

## (57)Abstract:

PURPOSE: To facilitate insertion and alignment of a suture prosthetic material adequate for use in an automatic suture device in surgical operation and to solve problems of mispositioning, etc., after mounting by forming a cloth body to a cylindrical shape, thereby forming the prosthetic material described above.

CONSTITUTION: This suture prosthetic material is formed by superposing non-woven fabrics 3 consisting of an in-vivo decomposable absorbent blank and a power net fabric 4 on each other and forming these fabrics to a cylindrical shape by subjecting both edge parts to chain stitching 5, 6. Both ends 7 of the sewing yarn are extended. The in-vivo decomposable absorbent blank includes a polyglycolic acid, polylactic acid, a copolymer of the glycolic acid and lactic acid, paradioxanone, polycaprolactone, chitin, etc.

The prosthetic material is mounted to the frame part 10 and cartridge part 9, respectively, of the suture device at the time of use. Both are then integrally fixed by staples in the state of holding the body tissues of the lesion between non-woven fabrics 3, 3 and the lesion 13 is ported. The power net fabric 4 is removed outside the body together with the lesion 13 by pulling the yarn ends 7.



## LEGAL STATUS

[Date of request for examination]

16.06.1997

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or

application converted registration]

[Date of final disposal for application]

[Patent number] 3136392

[Date of registration] 08.12.2000

[Number of appeal against examiner's decision  
of rejection]

[Date of requesting appeal against examiner's  
decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office